

| Ref # | Hits | Search Query | DBs | Default Operator | Plurals | Time Stamp |
|-------|------|--|------------------|------------------|---------|------------------|
| S2 | 7440 | (AFM STEM SEM nanotip\$3 probe atomic adj force scanning near microscope) and ((si silicon) near (n p dop\$4) n-type p-type) and etch\$3 | US-PGPU B; USPAT | OR | ON | 2005/09/28 11:22 |
| S3 | 1023 | S2 and (((si silicon) near (n dop\$4) n-type) with etch\$3) and (((si silicon) near (p dop\$4) p-type) with etch\$3) | US-PGPU B; USPAT | OR | ON | 2005/09/28 11:25 |
| S4 | 960 | S2 and (((si silicon) near (n dop\$4) n-type) with etch\$3) same (((si silicon) near (p dop\$4) p-type) with etch\$3) | US-PGPU B; USPAT | OR | ON | 2005/09/28 11:25 |
| S5 | 943 | S2 and (((si silicon) near (n dop\$4) n-type) with etch\$3) with (((si silicon) near (p dop\$4) p-type) with etch\$3) | US-PGPU B; USPAT | OR | ON | 2005/09/28 11:25 |
| S6 | 358 | S2 and (((si silicon) near n n-type) with etch\$3) with (((si silicon) near p p-type) with etch\$3) | US-PGPU B; USPAT | OR | ON | 2005/09/28 11:26 |
| S7 | 4 | S2 and (((si silicon) near n n-type) near etch\$3) with (((si silicon) near p p-type) near etch\$3) | US-PGPU B; USPAT | OR | ON | 2005/09/28 11:27 |
| S8 | 17 | S2 and (((si silicon) near n n-type) near2 etch\$3) with (((si silicon) near p p-type) near2 etch\$3) | US-PGPU B; USPAT | OR | ON | 2005/09/28 11:27 |
| S9 | 40 | S2 and (((si silicon) near n n-type) near4 etch\$3) with (((si silicon) near p p-type) near4 etch\$3) | US-PGPU B; USPAT | OR | ON | 2005/09/28 11:27 |

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| S10 | 46 | ("3977925" "4312117" "4668865" "4806755" "4943719").PN. OR ("5021364").URPN. | US-PGPU B; USPAT; USOCR | OR | OFF | 2005/09/28 11:38 |
| S11 | 13 | S8 not S7 | US-PGPU B; USPAT; EPO; JPO; DERWEN T; IBM_TDB | OR | OFF | 2005/09/28 11:43 |
| S12 | 23 | S9 not (S7 S8) | US-PGPU B; USPAT; EPO; JPO; DERWEN T; IBM_TDB | OR | OFF | 2005/09/28 11:43 |
| S13 | 5 | (cant?lever AFM STEM SEM nanotip\$3 probe atomic scanning microscope) near2 tip with ((si silicon) near (n p dop\$4) n-type p-type) with etch\$3 | US-PGPU B; USPAT | OR | ON | 2005/09/28 11:50 |
| S14 | 70 | ("3977925" "4307507" "4312117" "4668865" "4685996" "4806755" "4912822" "4916002" "4943719" "4968382" "4968585").PN. OR ("4943719" "5066358").URPN. | US-PGPU B; USPAT; USOCR | OR | OFF | 2005/09/28 11:52 |
| S16 | 92 | S10 S14 | US-PGPU B; USPAT; USOCR | OR | OFF | 2005/09/28 11:52 |
| S15 | 24 | S10 and S14 | US-PGPU B; USPAT; USOCR | OR | OFF | 2005/09/28 11:59 |

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| S17 | 68 | S16 not S15 | US-PGPU B; USPAT; USOCR | OR | OFF | 2005/09/28 11:59 |
| S18 | 28 | (US-5021364-\$ or US-5066358-\$ or US-4943719-\$ or US-6011261-\$ or US-5811017-\$ or US-5717132-\$ or US-5469733-\$ or US-5386720-\$ or US-5386110-\$ or US-5367165-\$ or US-5264696-\$ or US-6886395-\$ or US-6862921-\$ or US-6694805-\$ or US-6400166-\$ or US-6358426-\$ or US-6059982-\$ or US-5994160-\$ or US-5929643-\$ or US-5595942-\$ or US-5580827-\$ or US-5537863-\$ or US-5272913-\$ or US-5116462-\$ or US-4968585-\$ or US-4916002-\$).did. or (US-4685996-\$ or US-4307507-\$).did. | USPAT | OR | OFF | 2005/09/28 12:26 |

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| S19 | 18 | (US-6694805-\$ or US-6059982-\$ or US-6011261-\$ or US-5994160-\$ or US-5929643-\$ or US-5717132-\$ or US-5580827-\$ or US-5537863-\$ or US-5469733-\$ or US-5367165-\$ or US-5272913-\$ or US-5116462-\$ or US-5021364-\$ or US-4968585-\$ or US-4943719-\$ or US-4916002-\$ or US-4685996-\$ or US-4307507-\$).did. | USPAT | OR | OFF | 2005/09/28 12:32 |
| S21 | 0 | S20 and ((square rectang\$4 pyramid\$4) near (mask\$3 photoresist opening pit hole expos\$4)) and (deposit\$4 near (first second) near (dop\$3 si silicon)) and (etch\$3 near (Si silicon)) | US-PGPU B; USPAT | OR | ON | 2005/09/28 12:41 |
| S22 | 0 | S20 and ((square rectang\$4 pyramid\$4) near2 (mask\$3 photoresist opening pit hole expos\$4)) and (deposit\$4 near2 (first second) near2 (dop\$3 si silicon)) and (etch\$3 near2 (Si silicon)) | US-PGPU B; USPAT | OR | ON | 2005/09/28 12:41 |
| S23 | 8 | S20 and ((square rectang\$4 pyramid\$4) with (mask\$3 photoresist opening pit hole expos\$4)) and (deposit\$4 with (first second) near2 (dop\$3 si silicon)) and (etch\$3 with (Si silicon)) | US-PGPU B; USPAT | OR | ON | 2005/09/28 12:43 |

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|-----|------|--|------------------------|----|----|---------------------|
| S24 | 32 | S20 and ((square rectang\$4 pyramid\$4) with (mask\$3 photoresist opening pit hole expos\$4)) and (deposit\$4 with (first second) with (dop\$3 si silicon)) and (etch\$3 with (Si silicon)) | US-PGPU B; USPAT | OR | ON | 2005/09/28 12:44 |
| S26 | 4 | S25 and S24 | US-PGPU B; USPAT | OR | ON | 2005/09/28 12:44 |
| S27 | 3 | S23 and S25 | US-PGPU B; USPAT | OR | ON | 2005/09/28 12:44 |
| S28 | 4 | S26 S27 | US-PGPU B; USPAT | OR | ON | 2005/09/28 12:57 |
| S1 | 5998 | (AFM STEM SEM nanotip\$3 probe atomic adj force scanning near microscope) and (si near (n p dop\$4) n-type p-type) and etch\$3 | US-PGPU B; USPAT | OR | ON | 2005/09/28 12:58 |
| S30 | 4 | S29 and (n p dop\$4 n-type p-type) | US-PGPU B; USPAT | OR | ON | 2005/09/28 13:11 |
| S32 | 1 | S31 not S30 | US-PGPU B; USPAT | OR | ON | 2005/09/28 13:11 |
| S29 | 5 | S23 not S28 | US-PGPU B; USPAT | OR | ON | 2005/09/28 13:13 |
| S33 | 0 | S29 not S23 | US-PGPU B; USPAT | OR | ON | 2005/09/28 13:13 |

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| S34 | 24 | S24 not S23 | US-PGPU B; USPAT; EPO; JPO; DERWEN T; IBM_TDB | OR | OFF | 2005/09/28 13:15 |
| S36 | 0 | S35 not S34 | US-PGPU B; USPAT; EPO; JPO; DERWEN T; IBM_TDB | OR | ON | 2005/09/28 13:16 |
| S37 | 2 | S34 not S35 | US-PGPU B; USPAT; EPO; JPO; DERWEN T; IBM_TDB | OR | ON | 2005/09/28 13:16 |
| S35 | 22 | S34 and (p n p-type n-type dop\$4) | US-PGPU B; USPAT; EPO; JPO; DERWEN T; IBM_TDB | OR | ON | 2005/09/28 13:36 |
| S31 | 5 | S29 and (n p dop\$4 n-type p-type etch\$3) | US-PGPU B; USPAT | OR | ON | 2005/09/28 14:03 |
| S40 | 59 | S39 and (n p dop\$4 n-type p-type) | US-PGPU B; USPAT | OR | ON | 2005/09/28 14:03 |
| S41 | 207 | (n-type p-type dop\$3) near (Si silicon) with (\$6probe \$6tip stylus) | US-PGPU B; USPAT | OR | ON | 2005/09/28 14:55 |
| S25 | 38 | S20 and electrochemical\$2 with etch\$3 | US-PGPU B; USPAT | OR | ON | 2005/09/28 14:57 |

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| S42 | 23 | S41 and electrochemical\$2 with etch\$3 | US-PGPU B; USPAT | OR | ON | 2005/09/28 14:57 |
| S38 | 22 | S34 and (p n p-type n-type dop\$4) | US-PGPU B; USPAT | OR | ON | 2005/09/28 15:07 |
| S43 | 23 | S42 and (p n p-type n-type dop\$4) | US-PGPU B; USPAT | OR | ON | 2005/09/28 15:07 |
| S39 | 83 | ("3977925" "4008412" "4307507" "4312117" "4668865" "4724318" "4806755" "5057047" "5214282" "5272330" "5354985" "5357787" "5410151" "5489774" "5580827" "5811926"). PN. OR ("4943719" "5883387" "5962958"). URPN. | US-PGPU B; USPAT; USOCR | OR | OFF | 2005/09/28 15:21 |
| S45 | 17 | (n-type p-type dop\$3) near (Si silicon) near (\$2AFM \$6probe \$6tip stylus) | US-PGPU B; USPAT | OR | ON | 2005/10/03 15:36 |
| S46 | 1 | deposit\$4 near (n-type p-type dop\$3) near (Si silicon) near (\$2AFM \$6probe \$6tip stylus) | US-PGPU B; USPAT | OR | ON | 2005/10/03 15:38 |
| S48 | 1 | deposit\$4 near4 (n-type p-type dop\$3) near4 (Si silicon) near4 (\$2AFM \$6probe \$6tip stylus) | EPO; JPO; DERWEN T; IBM_TDB | OR | ON | 2005/10/03 15:43 |
| S49 | 56 | deposit\$4 same (n-type p-type dop\$3) same (Si silicon) same (\$2AFM \$6probe \$6tip stylus) | EPO; JPO; DERWEN T; IBM_TDB | OR | ON | 2005/10/03 15:43 |
| S47 | 11 | deposit\$4 near4 (n-type p-type dop\$3) near4 (Si silicon) near4 (\$2AFM \$6probe \$6tip stylus) | US-PGPU B; USPAT | OR | ON | 2005/10/03 16:00 |

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| S50 | 42 | deposit\$4 with (n-type p-type dop\$3) with (Si silicon) with (\$2AFM \$6probe \$6tip stylus) | US-PGPU B; USPAT | OR | ON | 2005/10/03 16:01 |
| S51 | 31 | S50 not S47 | US-PGPU B; USPAT | OR | ON | 2005/10/03 16:01 |
| S53 | 123 | dop\$3 near (Si silicon) with (\$2AFM \$6probe \$6tip stylus) | US-PGPU B; USPAT | OR | ON | 2005/10/03 16:32 |
| S44 | 218 | (n-type p-type dop\$3) near (Si silicon) with (\$2AFM \$6probe \$6tip stylus) | US-PGPU B; USPAT | OR | ON | 2005/10/03 16:33 |
| S55 | 74 | S54 and electrochemical\$2 near4 etch\$3 | US-PGPU B; USPAT | OR | ON | 2005/10/03 16:34 |
| S56 | 48 | S55 not S52 | US-PGPU B; USPAT | OR | ON | 2005/10/03 16:34 |
| S52 | 26 | S44 and electrochemical\$2 near4 etch\$3 | US-PGPU B; USPAT | OR | ON | 2005/10/03 16:39 |
| S54 | 1336 | (n-type p-type dop\$3) with (Si silicon) same (\$2AFM \$6probe \$6tip stylus) | US-PGPU B; USPAT | OR | ON | 2005/10/03 16:39 |
| S57 | 194 | (n-type p-type dop\$3) with (Si silicon) same (\$2AFM \$6probe \$6tip stylus) | EPO; JPO; DERWEN T; IBM_TDB | OR | ON | 2005/10/03 16:39 |
| S58 | 0 | S57 and electrochemical\$2 near4 etch\$3 | US-PGPU B; USPAT | OR | ON | 2005/10/03 16:39 |
| S59 | 5 | S57 and electrochemical\$2 near4 etch\$3 | EPO; JPO; DERWEN T; IBM_TDB | OR | ON | 2005/10/03 16:39 |